

[ThB1] Structural Analysis

Session Date	July 16 (Thu.), 2026
Session Time	08:30–10:15
Session Room	Room B (Baekrok Hall B, 1F)
Session Chairs	Dr. Masanobu Hiroki (NTT Inc., Japan), Prof. Soon-Ku Hong (Chungnam University, Korea)

[ThB1–1] [Invited]

08:30–09:00

MOVPE Growth of AlGa_N with Step-and-Terrace Structures on AlN Templates

Ryota Akaike, Hiroki Yasunaga, Takao Nakamura, and Hideto Miyake, Mie University, Japan

[ThB1–2]

09:00–09:15

Atomic Structure of Antiphase Domain Boundaries in III–V Semiconductor Layers Epitaxially Grown on Silicon (100) or Obtained by Direct Wafer Bonding

Gilles Patriarche¹, Konstantinos Pantzas¹, Alexandre Beck², Laurent Pedesseau², Rozenn Gautheron-Bernard², Nathaniel Findling¹, Ludovic Largeau¹, Grégoire Beaudoin¹, Jean-Baptiste Rodriguez³, Eric Tournié³, Isabelle Sagnes¹, and Charles Cornet², ¹Centre national de la recherche scientifique, France, ²Institut National des Sciences Appliquées de Rennes, France, ³Université de Montpellier, France

[ThB1–3]

09:15–09:30

Interplay of Carrier Recombination and Separation in an InGa_N MQW LED Investigated by Nano-STEM-EBIC and -STEM-CL

Niklas Dreyer, Frank Bertram, Gordon Schmidt, Luca Greczmiel, Christoph Berger, Armin Dadgar, André Strittmatter, and Jürgen Christen, Otto-von-Guericke-University Magdeburg, Germany

[ThB1–4]

09:30–09:45

Vacancy Properties and Their Clustering in GaN MOVPE Epitaxial Layers and Heterostructures

Alice Hospodková¹, Jakub Čížek², František Hájek¹, Karla Kuldová¹, Tomáš Hubáček¹, Jiří Pangrác¹, Maciej Oskar Liedke³, Eric Hirschmann³, Maik Butterling³, and Andreas Wagner³, ¹Institute of Physics of the Czech Academy of Sciences, Czech Republic, ²Charles University, Czech Republic, ³Helmholtz-Zentrum Dresden-Rossendorf, Germany

[ThB1–5]

09:45–10:00

Revisiting the Stacking Faults in 4H-SiC

Soon-Ku Hong¹, Moonkyong Na², Hyundon Jung³, and Wook Bahng², ¹Chungnam National University, Korea, ²Korea Electrotechnology Research Institute, Korea, ³Horiba STEC Korea, Korea

[ThB1–6]

10:00–10:15

Analytical X-Ray Solutions for Thin Film and Wafer Analysis

Andrey Zameshin¹, Alexey Pustovarenko¹, Amardeep Bharti¹, Choong Ki (Daniel) Lee², and Shuji Kusano³, ¹Malvern Panalytical, Netherlands, ²Spectris Korea Ltd, Korea, ³Spectris Co. Ltd, Japan